

Fig. 1. InO_x film growth characteristics of (a) ALD temperature window, (b) linear ALD growth, and (c) bottom step coverage at 40:1 A/R structure depending on the type of oxidants.

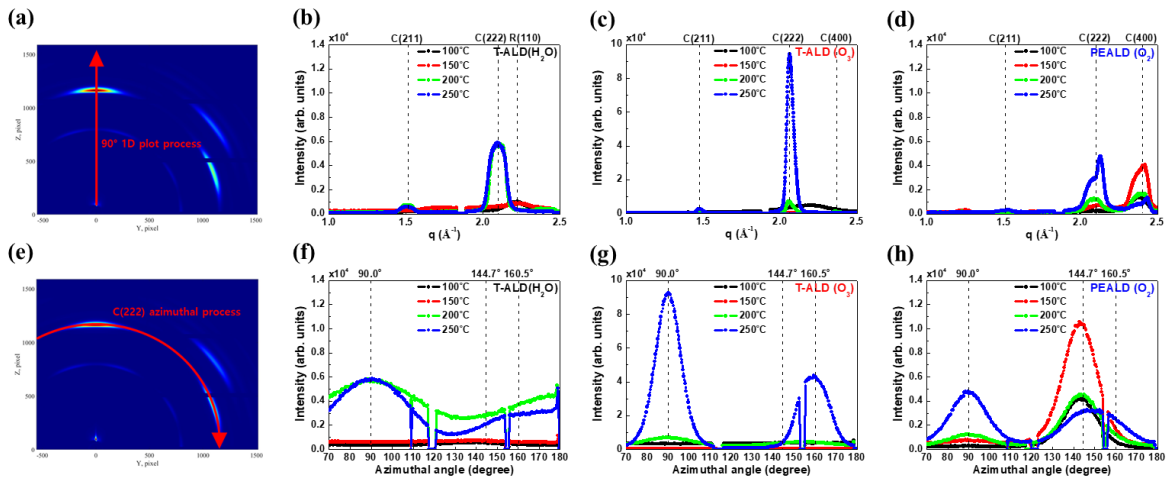


Fig. 2. (a) 90° 1D plot process example of GI-WAXS and the data of (b) T-ALD (H₂O), (c) T-ALD (O₃), and (d) PEALD (O₂) InO_x. (e) C(222) azimuthal process example of GI-WAXS and the data of (f) T-ALD (H₂O), (g) T-ALD (O₃), and (h) PEALD (O₂) InO_x.